

	Type	L #	Hits	Search Text	DBs	Time Stamp	Comments
1	BRS	L1	873	(wafer substrate) same (inert adj gas argon) same rough\$4	USPAT; US-PGPUB ; EPO; JPO; DERW ENT; IBM TDB	2003/10/07 15:59	
2	BRS	L2	242	(wafer substrate) same (inert adj gas argon) same rough\$4 and (Cr chromium)	USPAT; US-PGPUB ; EPO; JPO; DERW ENT; IBM TDB	2003/10/07 16:03	